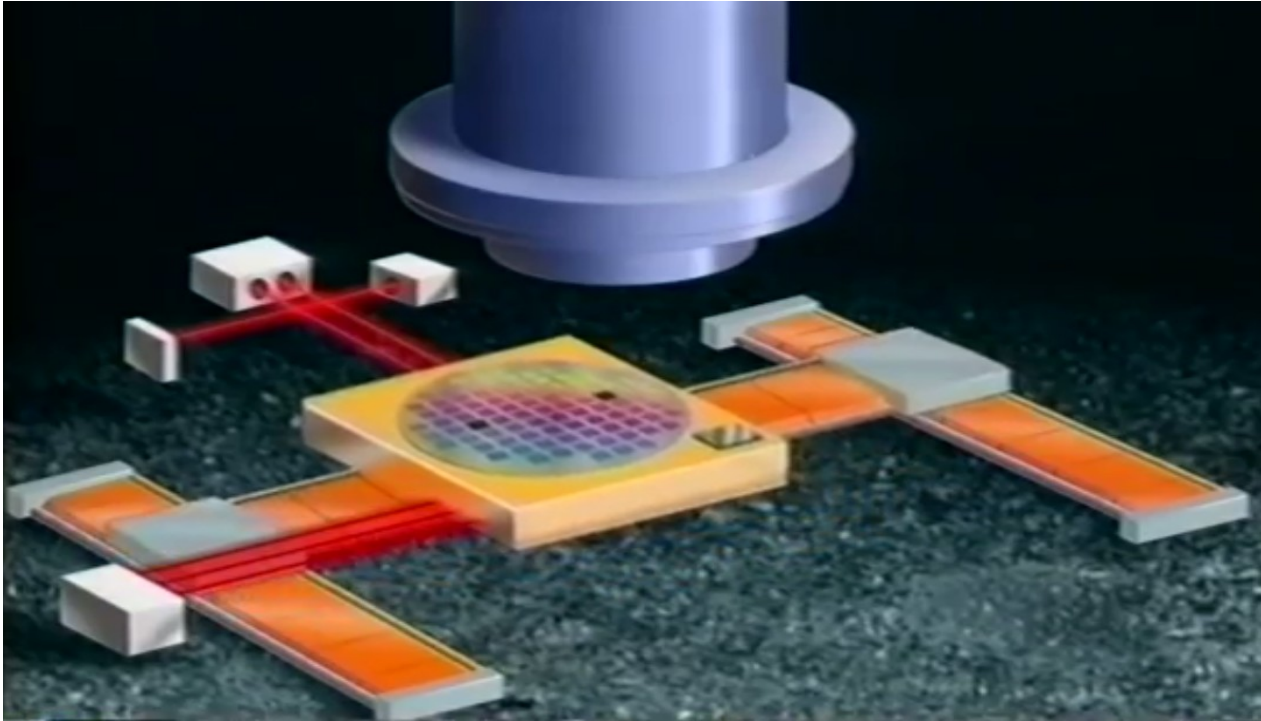
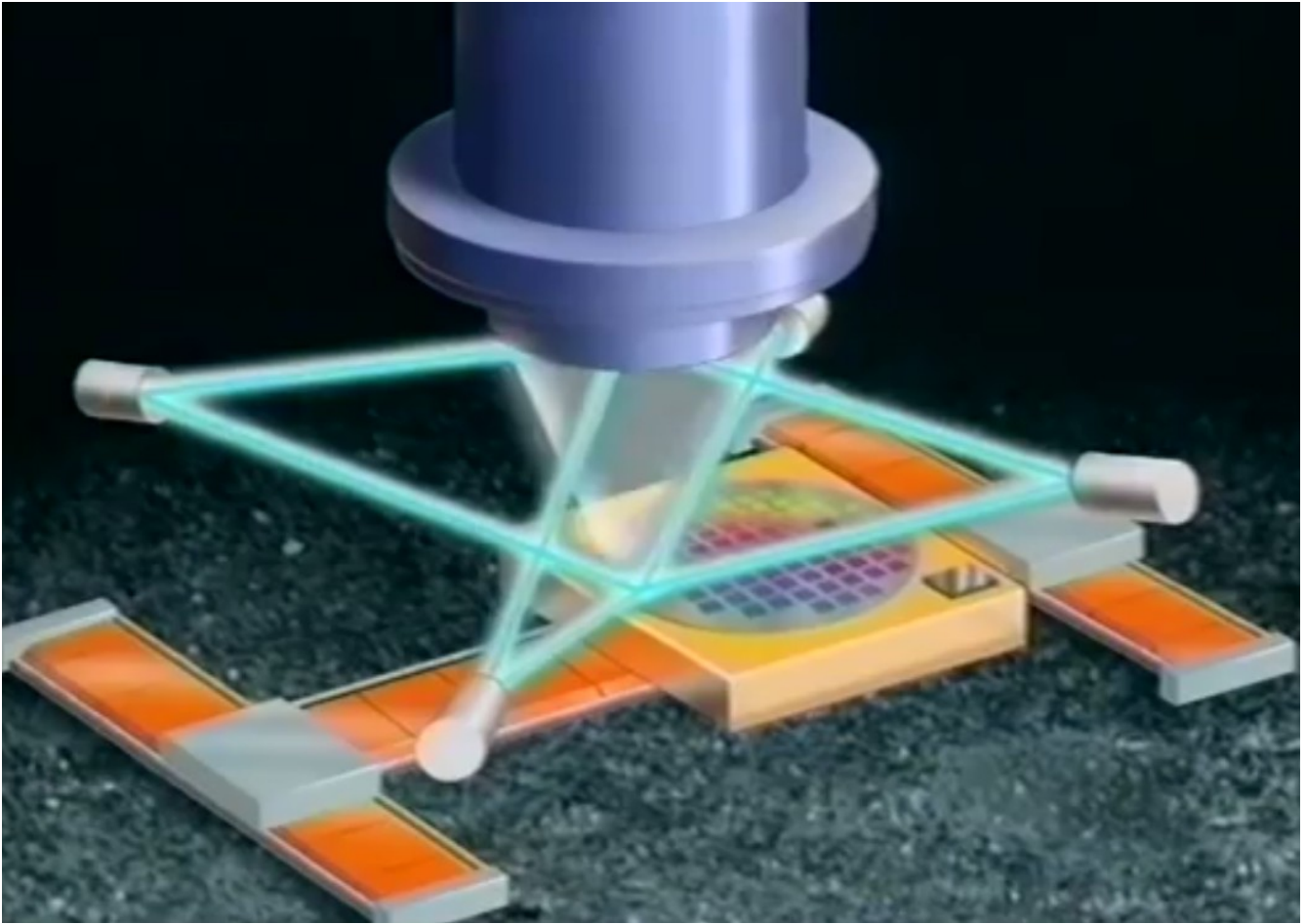


Stepper/Scanner

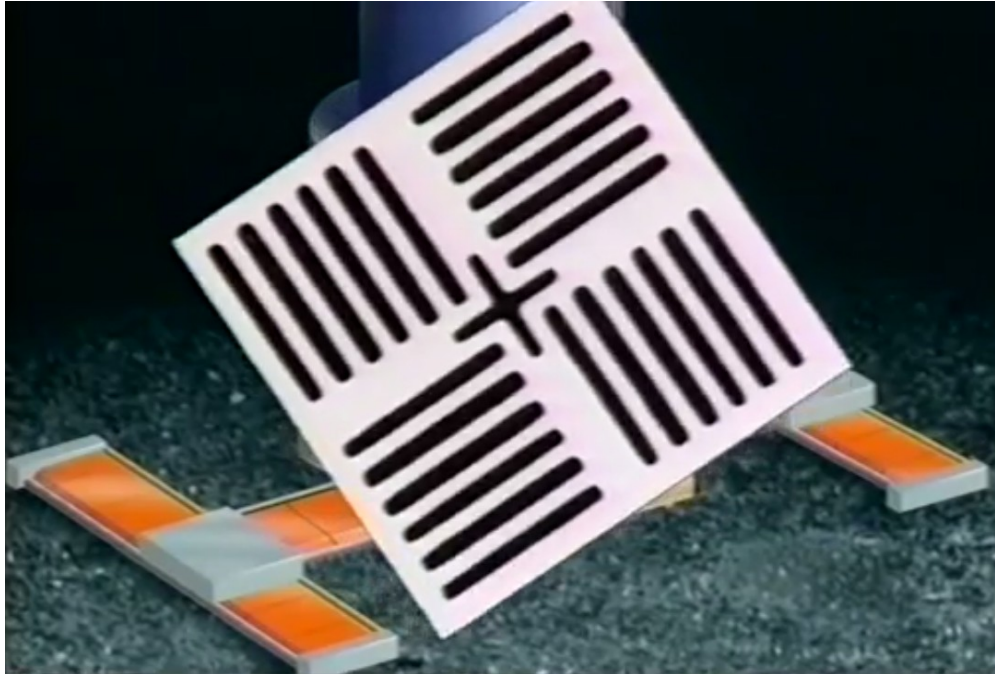


6 -Axis (6 laser light) Interferometer used to control the position of the Wafer.
Accuracy of the movement of the wafer is down to 5nm.

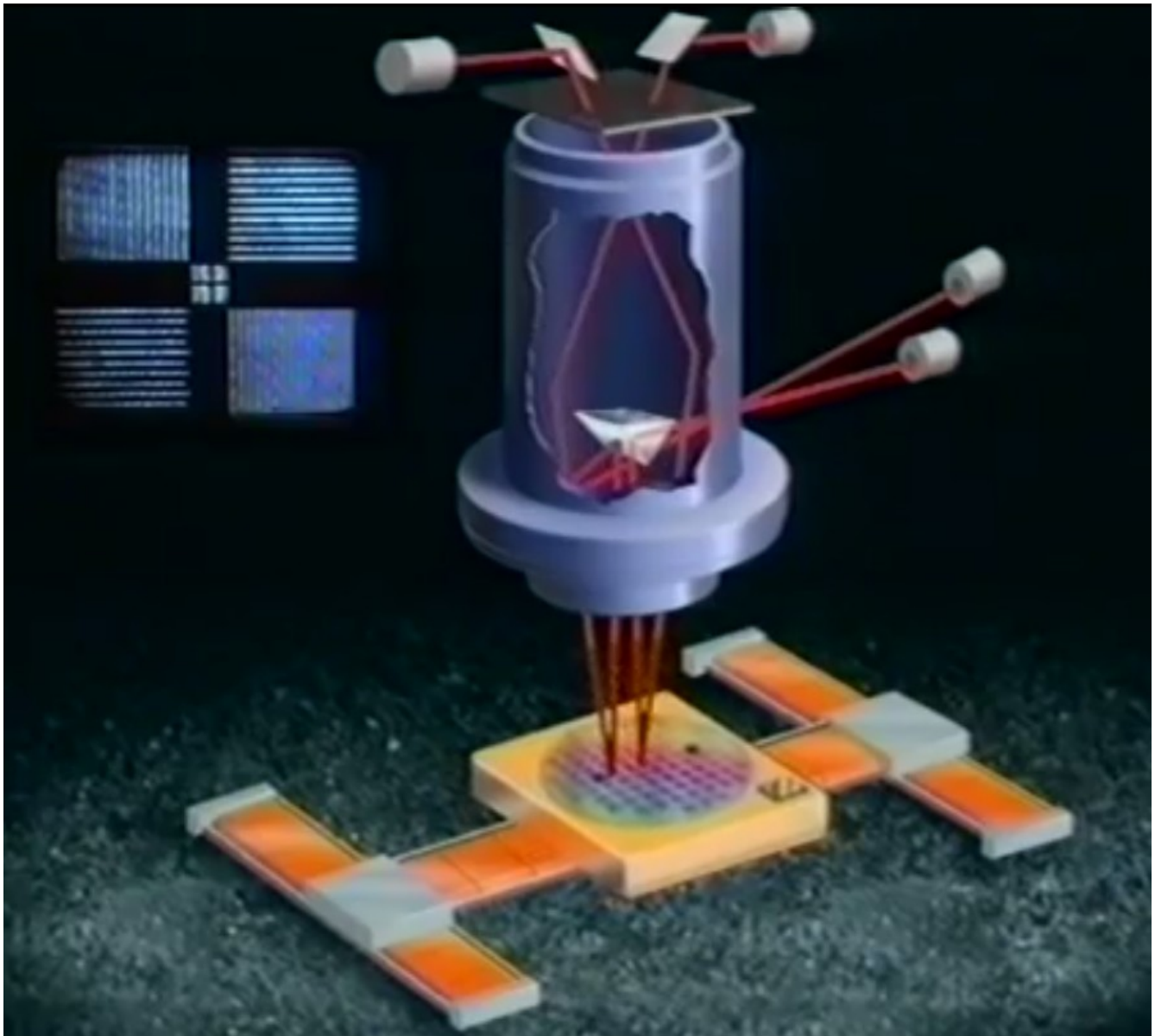


Field by Field leveling takes place automatically before each exposure

Alignment



Face grating Technology



Dual Laser Beam method to search face grating markers. Both vertical and horizontal lines are used in the face grating for alignment.

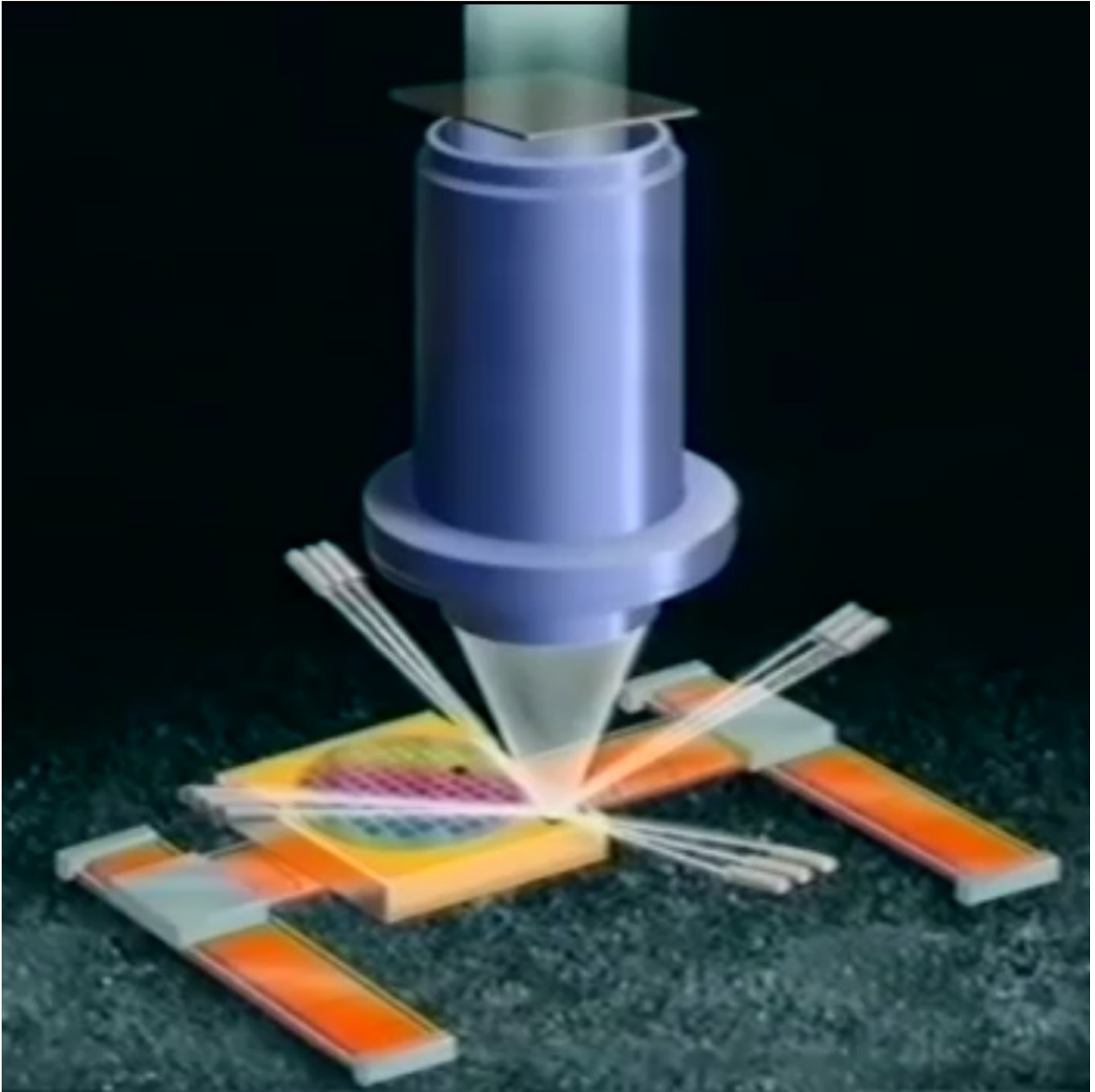
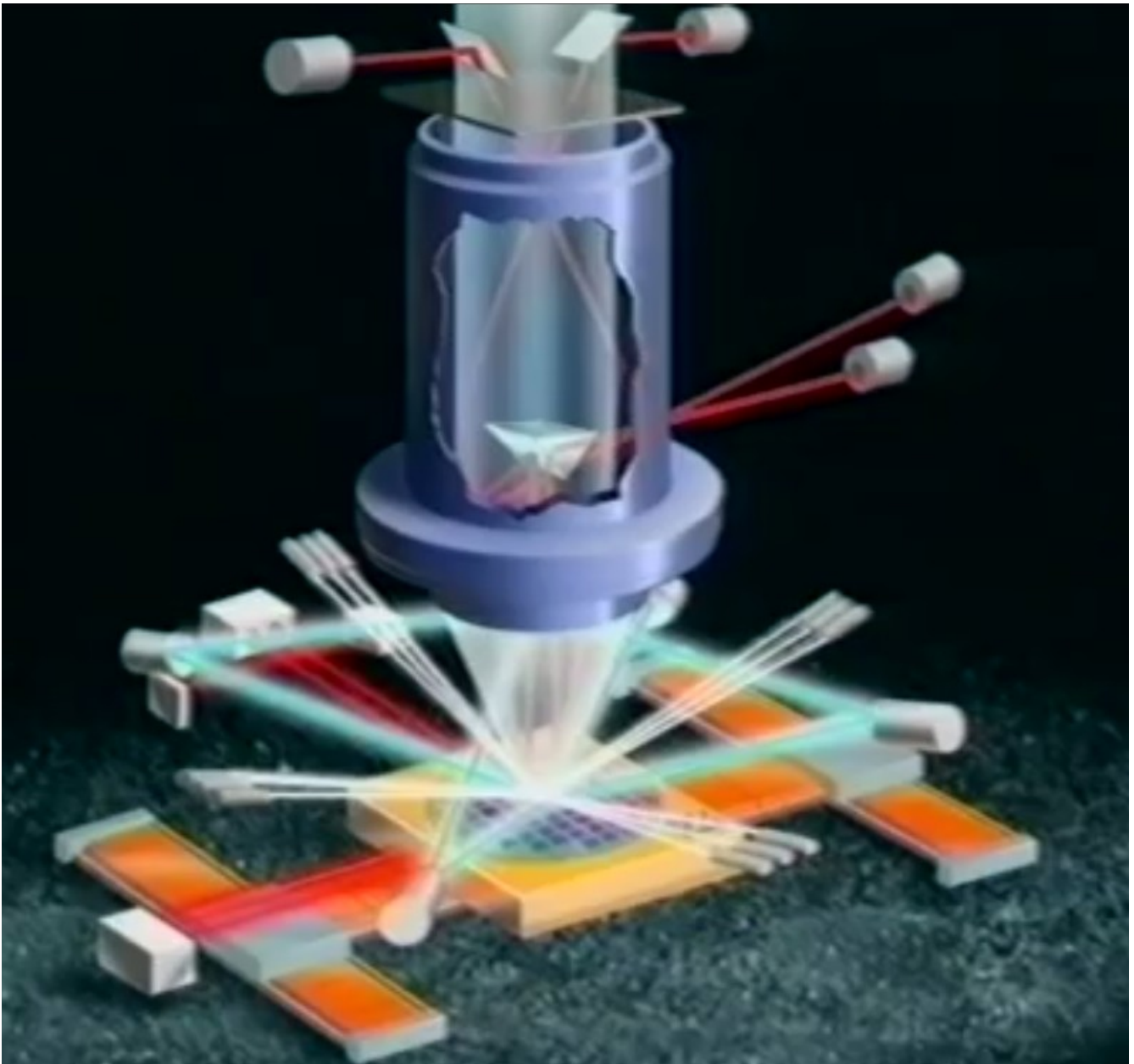


Image sensors are also used additionally for fast alignment.



All these together, interferometers and image sensors for fast accuracy and productivity.